

Amendments to the Claims:

This listing of claims replaces all prior versions and listings of claims in the application.

In the Claims:

1. (Currently Amended) A device for holding a nanolithography template used for imprinting a nanolithography pattern on a substrate, said the device comprising:

a body having an opening to receive said the nanolithography template, said the body for positioning said the template relative to said the substrate for imprinting said the nanolithography pattern on said the substrate; and

a supporting plate coupled to said the body and positioned relative to said the nanolithography template to support a force of said the imprinting on said the nanolithography template, with said the supporting plate being substantially transparent to a curing agent; and,

a piezo system coupled to the body to vary dimensions of the nanolithography template.

2. (Currently Amended) The device as recited in claim 1 wherein said the curing agent comprises ultraviolet radiation.

3. (Currently Amended) The device as recited in claim 1 wherein said the supporting plate is formed from material selected from a set of materials consisting of quartz, sapphire, and silicon dioxide.

4. (Currently Amended) The device as recited in claim 1 further including a vacuum system in fluid communication with said the supporting plate to apply a vacuum to said the nanolithography template.

5. (Currently Amended) The device as recited in claim 1 further including a vacuum system in fluid communication with said the supporting plate to apply a vacuum between said the supporting plate and said the body.

6. (Currently Amended) The device as recited in claim 1 wherein said the supporting plate is configured to reduce deformation of said the nanolithography template due to forces present during an imprint lithography process.

7. (Currently Amended) The device as recited in claim 1 further including a reflective element connected to a portion of said the body located within said the opening.

8. (Currently Amended) A device for holding a nanolithography template used for imprinting a nanolithography pattern on a substrate, said the device comprising:

a body having an opening to receive said the nanolithography template, said the body for positioning said the template relative to said the substrate for imprinting said the nanolithography pattern on said the substrate; and

a supporting plate coupled to said the body and positioned relative to said the nanolithography template to support a force of said the imprinting on said the nanolithography template, with said the supporting plate substantially transparent to ultraviolet radiation; and,

a piezo system coupled to said body to vary dimensions of said nanolithography template.

9. (Currently Amended) The device as recited in claim 8 wherein said the supporting plate is formed from material selected from a set of materials consisting of quartz, sapphire, and silicon dioxide.

10. (Currently Amended) The device as recited in claim 8 further including a vacuum system in fluid communication with said the supporting plate to apply a vacuum to said the nanolithography template.

11. (Currently Amended) The device as recited in claim 8 further including a vacuum system in fluid communication with said the supporting plate to apply a vacuum between said the supporting plate and said the body.

12. (Currently Amended) The device as recited in claim 8 wherein said the supporting plate is configured to reduce deformation of said the nanolithography template due to forces present during an imprint lithography process.

13. (Currently Amended) The device as recited in claim 8 further including a reflective element connected to a portion of said the body located within said the opening.

14. (Currently Amended) A device for holding a nanolithography template used for imprinting a nanolithography pattern on a substrate, said the device comprising:

a body having an opening to receive said the nanolithography template, said the body for positioning said the template relative to said the substrate for imprinting said the nanolithography pattern on said the substrate;

a supporting plate coupled to said the body and positioned relative to said the nanolithography template to support a force of said the imprinting on said the nanolithography template, with said the supporting plate substantially transparent to a curing agent

a piezo system coupled to said body to vary dimensions of said nanolithography template; and

a vacuum system in fluid communication with said the supporting plate to apply a vacuum between said the supporting plate and said the body.

15. (Currently Amended) The device as recited in claim 14 wherein said the curing agent comprises ultraviolet radiation.

16. (Currently Amended) The device as recited in claim 14 wherein said the supporting plate is formed from material selected from a set of materials consisting of quartz, sapphire, and silicon dioxide.

17. (Currently Amended) The device as recited in claim 14 wherein said the supporting plate is configured to reduce deformation of said the nanolithography template due to forces present during an imprint lithography process.

18. (Currently Amended) The device as recited in claim 14 further including a reflective element connected to a portion of said the body located within said the opening.